

RETAINING RING WITH TRIGGER FOR CHEMICAL MECHANICAL POLISHING APPARATUS.

ABSTRACT OF THE DISCLOSURE

5 A retaining ring for chemical mechanical polishing (CMP) apparatus
comprising a body of the retaining ring, and a single trigger cavity, or a plurality
of trigger cavities. Each trigger cavity formed inside the body of the retaining
ring is filed with gas or fluid, and is configured to indicate that thickness of the
10 retaining ring is less than or equal to a predetermined thickness threshold.